

In the Claims:

Please cancel claim 27. ✓

Please amend claims 1, 2, 12, 22, 25, 26, and 28 as follows:

1. (Currently Amended) A no-flow underfill material comprising:
- an epoxy [SiloxiraneTM]-based resin including oxirane grafted silica particles;
- at least one agent acting as a cross-linking hardener and a curing catalyst capable of catalyzing the curing of the epoxy-based resin; and
- a fluxing agent.
2. (Currently Amended) The material of claim 1 wherein the epoxy- [SiloxiraneTM] based resin is represented by:



where R1 includes SiO₂

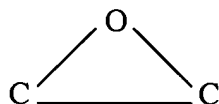
R2 is a reactive organic functional group, and

R3 is an organic chain segment.

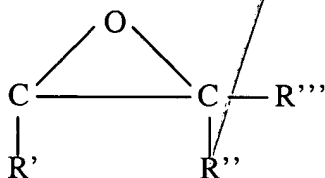
3. (Original) The material of claim 2 wherein R1 is a surface-grafted fused silica particle with a size less than 50 microns.
4. (Previously Amended) The material of claim 3 wherein a structure of R1 is made cyclic.

5. (Original) The material of claim 2 wherein R1 includes an oxygen atom linked to the silica particle, R3 being linked to the oxygen atom.

6. (Previously Amended) The material of claim 2 wherein R2 includes an oxirane group represented by:

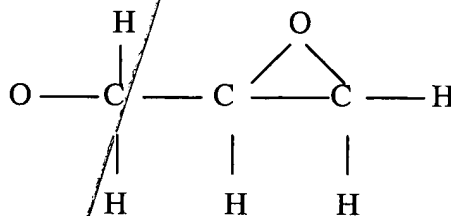


7. (Previously Amended) The material of claim 6 wherein R2 is represented by:

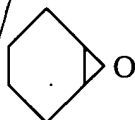


Wherein R', R'', and R''' are hydrogen or alkyl groups.

8. (Previously Amended) The material of claim 7 wherein R2 is represented by:



or



9. (Original) The material of claim 1 wherein the agent acting as a cross-linking hardener and a catalyst includes both a hardener and a catalyst.

10. (Previously Amended) The material of claim 1 wherein the cross-linking hardener is selected from the group consisting of an imidazole and its derivatives, an amine, a triphenylphosphine, an anhydride, a polyamide, a polyamide amine, a phenolic resin, and an onium salt.

11. (Original) The material of claim 1 wherein the catalyst is selected from the group consisting of an imidazole and its derivatives, an imidazolium salt, a triphenylphosphine, a tertiary amine, and an onium salt.

12. (Currently Amended) The material of claim 1 wherein the fluxing agent is dissolved in a mixture of the epoxy [SiloxiraneTM]-based resin and the agent acting as a cross-linking hardener.

13. (Original) The material of claim 1 wherein the fluxing agent is selected from the group consisting of an organic carboxylic acid, a polymeric fluxing agent, and an organic compound that contains one or more hydroxyl groups.

14. (Original) The material of claim 1 further comprising:
an adhesion promoter.

15. (Original) The material of claim 14 wherein the adhesion promoter is selected from the group consisting of a silane coupling agent, an organo-ziconate, and an organo-titanate.

16. (Original) The material of claim 1 further comprising:
a non-ionic surfactant.

17. (Previously Amended) The material of claim 16 wherein the surfactant is selected from the group consisting of polyol, a siloxane compound, and a fluorinated compound.

18. (Original) The material of claim 1 further comprising:
fused silica.

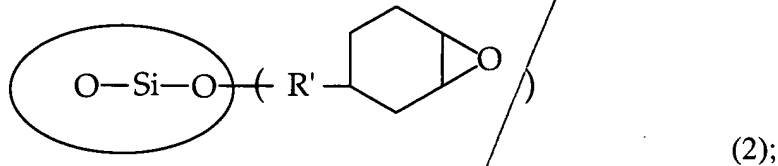
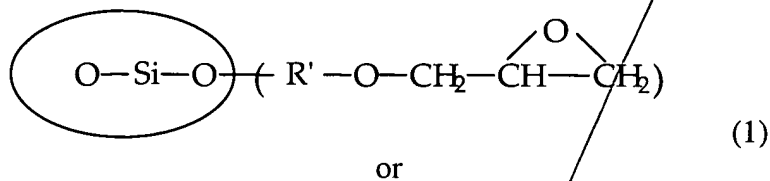
19. (Original) The material of claim 1 further comprising:
silver flakes.

20. (Original) The material of claim 1 further comprising:
thermally conductive particles.

21. (Original) The material of claim 20 wherein the thermally conductive particles include a material selected from the group consisting of silicon nitride, silicon borate, alumina, diamond, and silicon oxide.

22. (Currently Amended) A no-flow underfill material comprising:

an epoxy resin including oxirane grafted silica particles and being represented by



at least one agent acting as a cross-linking hardener and a curing catalyst capable of catalyzing the curing of the epoxy resin; and a fluxing agent.

23. (Previously Amended) The no-flow underfill material of claim 22 further comprising:

an adhesion promoter;

a non-ionic surfactant;

fused silica;

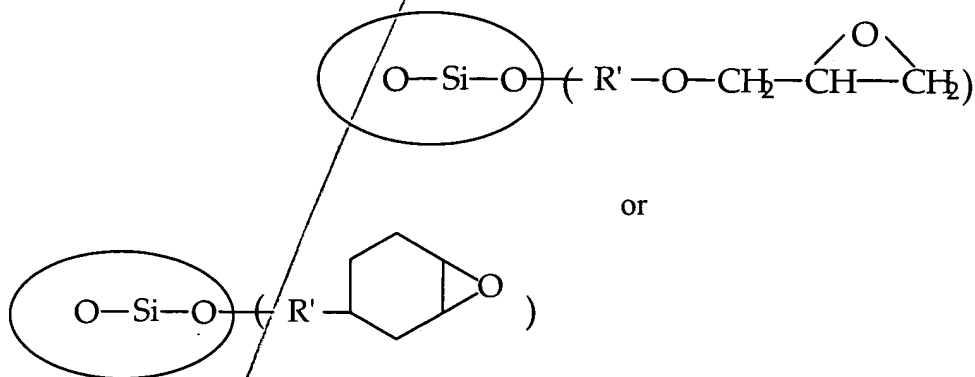
silver flakes; and

thermally conductive particles.

24. (Original) The no-flow underfill material of claim 22 wherein the agent acting as a cross-linking hardener and a catalyst includes both a hardener and a catalyst.

25. (Currently Amended) A semiconductor package comprising:
a package substrate;
bond pads on the substrate;
a semiconductor die;
contact pads on the semiconductor die;
a respective conductive bump on each contact pad, the die being located so that each bump is in contact and attached to a respective bond pad; and
an underfill material filling regions between the bumps and including at least an epoxy [SiloxiraneTM]-based resin including oxirane grafted silica particles.

26. (Currently Amended) The semiconductor package of claim 25 wherein the epoxy [SiloxiraneTM]-based resin is represented by:



27. Cancelled

28. (Currently Amended) A semiconductor package comprising:

a package substrate;

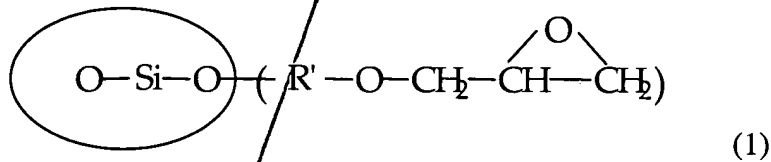
bond pads on the substrate;

a semiconductor die;

contact pads on the semiconductor die;

a respective conductive bump on each contact pad, the die being located so that each bump is in contact and attached to a respective bond pad; and

an underfill material filling regions between the bumps and including at least an epoxy-based resin including oxirane grafted silica particles, and being represented by:



or

